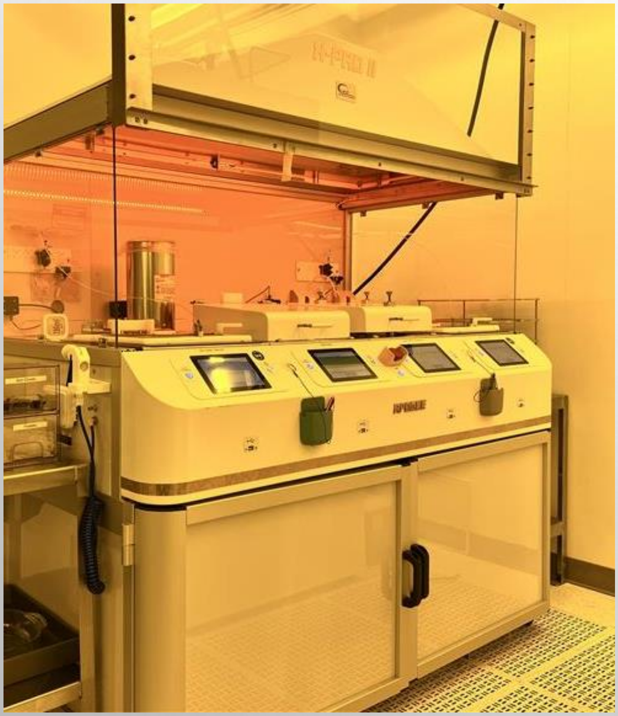
Cee spin coater workstation: Spin Coater, Bake Plate and Vapor HMDS Bake Plate

All in one: Spin Coater, Bake Plate, Vapor HMDS Bake Plate

- ❇ High-quality and uniform spin coating results
- ❇ Automatic edge bead removal and backside rinse
- ❇ One-button vapor HMDS coating for superior adhesion promotion
- ❇ Fully programmable recipes and ease of use



Spin coater:

- Substrate sizes: up to 200 mm
- Spin speed repeatability: 0.2 rpm
- Acceleration resolution < 0.2 rpm/s
- Edge bead removal and backside rinse

Bake plate:

- Temperature resolution: 0.1°C
- Temperature uniformity: ± 0.3% across working surface
- Built-in timer for precise, automated baking control

Vapor HMDS Bake plate:

- One-button vapor HMDS coating process

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